

ADDITIVE FOR PHOTSENSITIVE RESIN AND THAT FOR UNDERCOAT OF PHOTSENSITIVE RESIN

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Abstract of JP3064753

PURPOSE:To enhance high temperature treatment characteristics and solubility in organic solvents and light absorbance in the shorter or longer sides of a specified wavelength region by adding a specified triazole derivative to the photosensitive resin and the undercoat material of the photosensitive resin.

CONSTITUTION:The photosensitive resin and its undercoat material contain the triazole derivative represented by formula I in which each of R and R' is independently H, halogen, optionally substituted alkyl, such alkoxy, or such alkylamino, and oen of R and R' is optionally substituted alkylamino; m is 1 - 5; and n is 1 - 4. It is preferred to add this derivative in an amount of 1 - 40wt.%, especially 3 - 35wt.%, thus permitting high temperature treatment characteristics, solubility in organic solvents, and absorbances in the shorter side and the longer side of the specified wavelength region to be enhanced.

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